Choosing Figures That Clearly Make Your Point

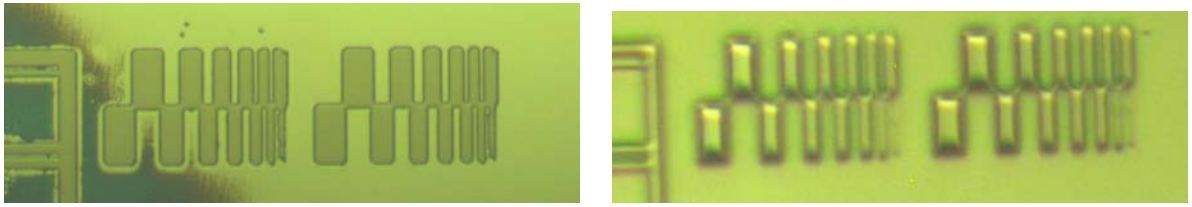

Figure 1. Photoresist exposed for 10 seconds a) before etching b) after etching

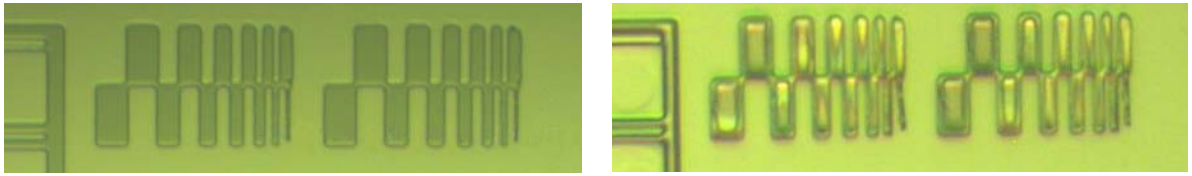

Figure 2. Photoresist exposed for 20 seconds a) before etching b) after etching

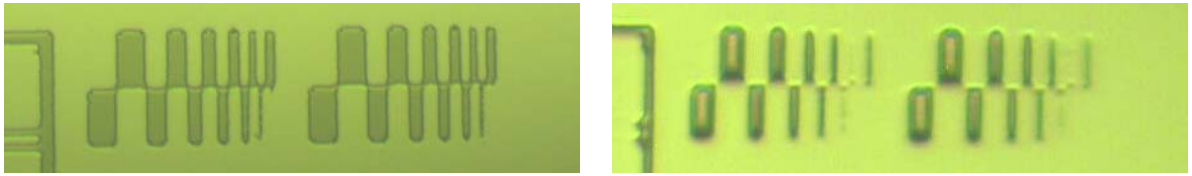

Figure 3. Photoresist exposed for 45 seconds a) before etching b) after etching

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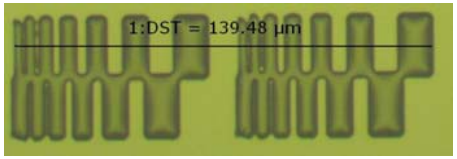
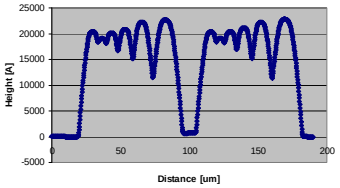
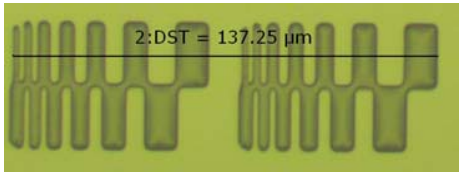
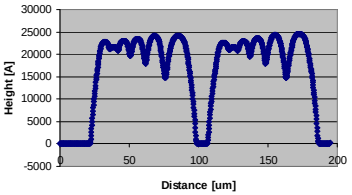


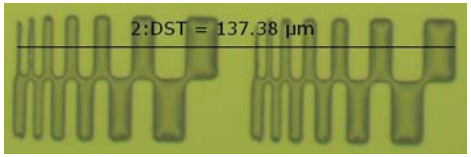


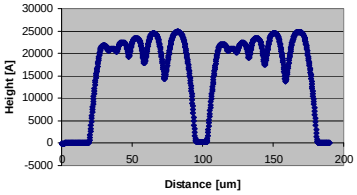
(a) 10s exposure





(a) 20s exposure





(a) 30s exposure

Figure 1: Pictures for different exposure times, (a) 10s, (b) 20s, and (c) 30s, respectively.

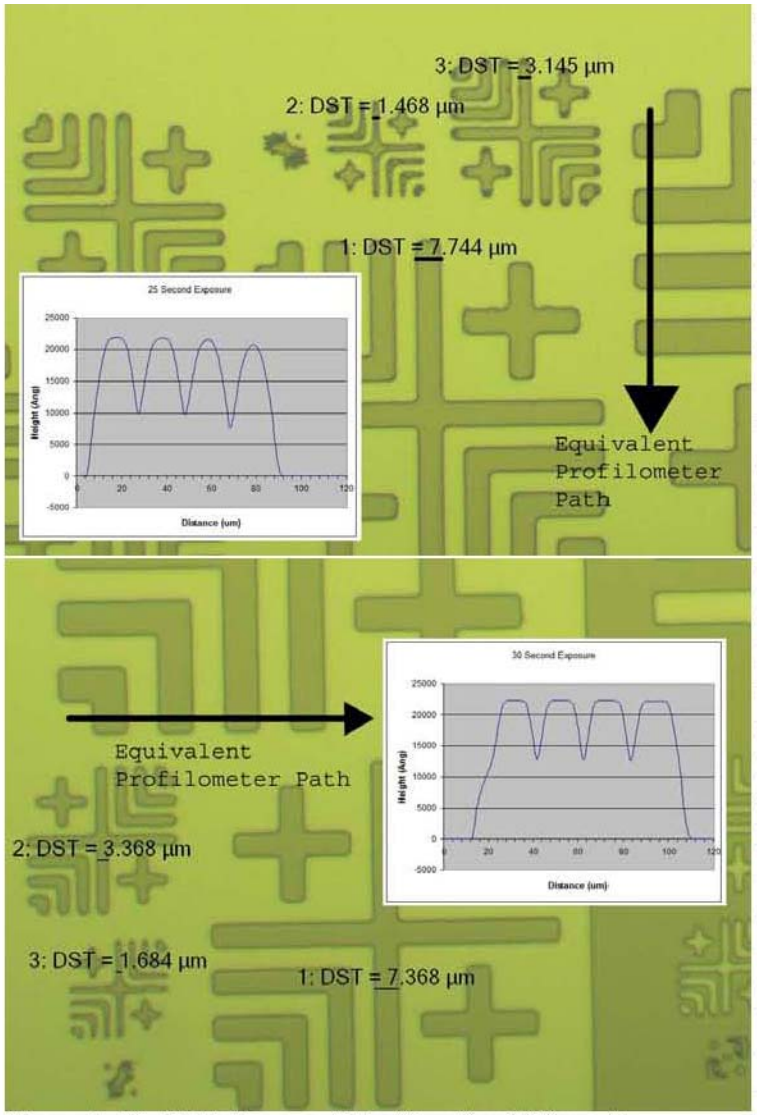


Figure 1: Resist Patterns and Profiles after 20 Seconds Exposure (Top), 25 Seconds Exposure (Middle), and 30 Seconds Exposure (Bottom).

Clearly showing the sequence of events: lithography, etching, how does the resist stand up to the process?

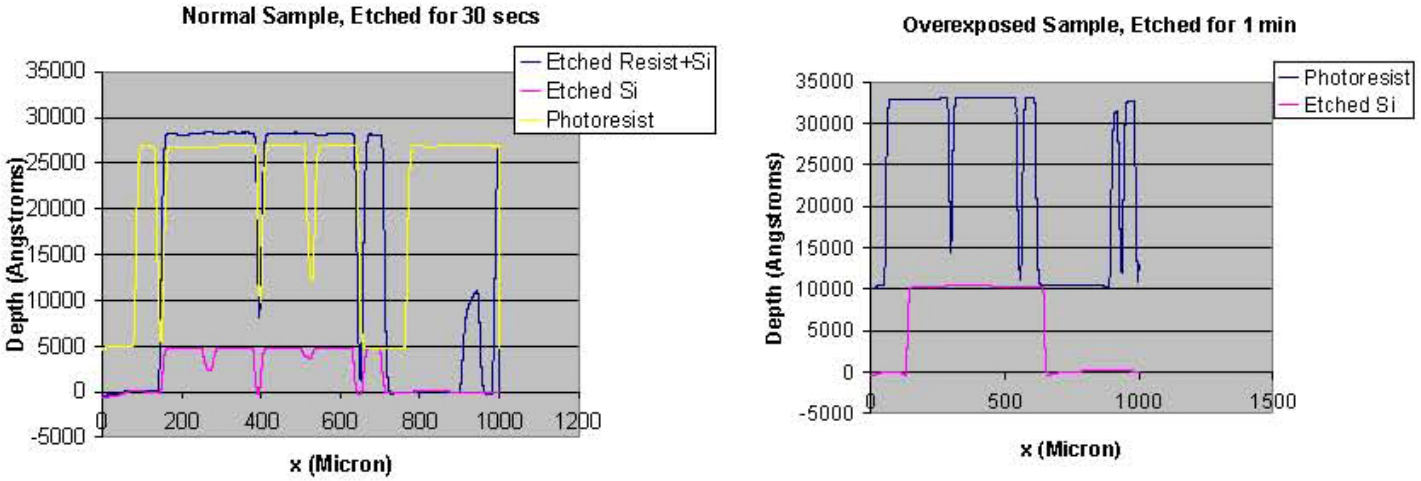
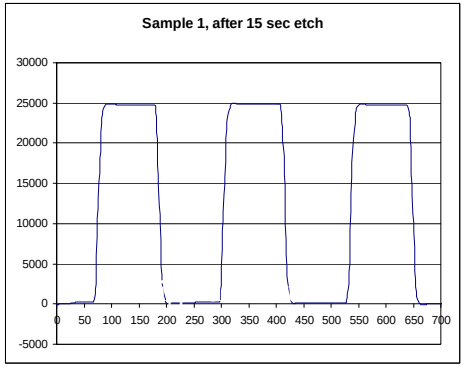
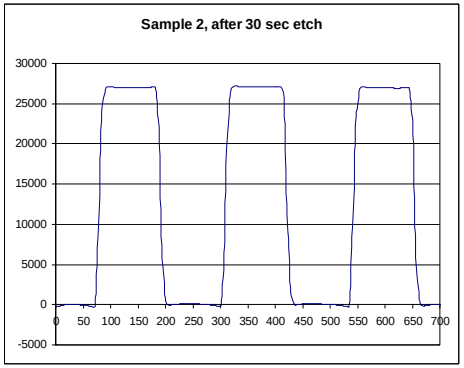


Figure 3) Dektak results of two prepared samples, Left) Normal sample that is etched for 30 seconds, and Right) is the Over Exposed sample that is etched for 60 seconds.

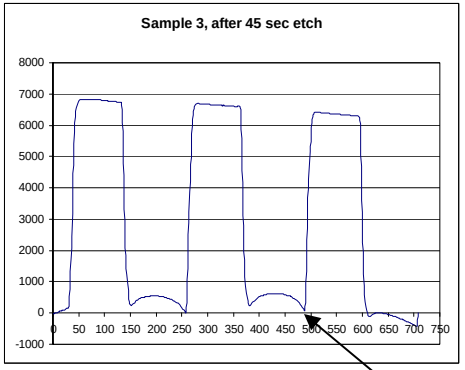
Attention to detail



15s etch

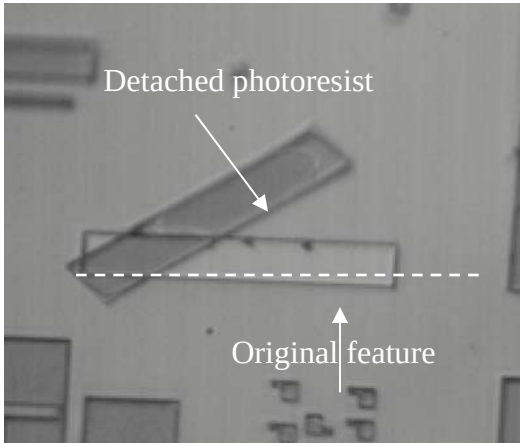


30s etch



45s etch

'trenching'



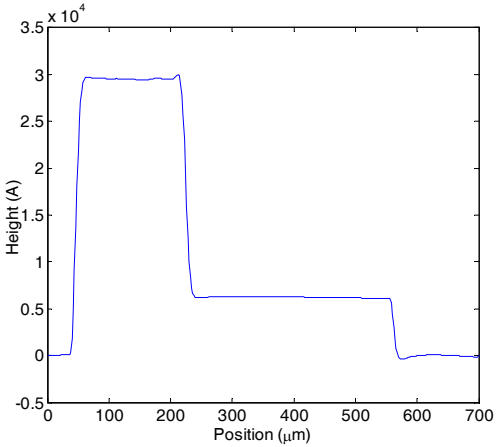


Figure 5. a) Feature and detached photoresist b) cross-sectional profile of feature and detached resist along dotted white line in (a).